Electronic Supplementary Information (ESI)

## NH<sub>3</sub> assisted Photoreduction and N-doping of Graphene oxide as High Performance of Electrode Material for Supercapacitors Application

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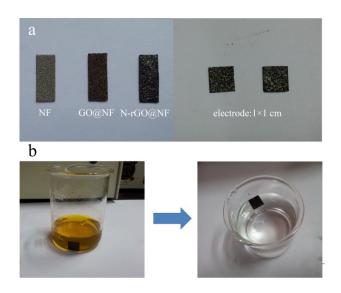


Fig. S1 (a) Digital photographs of nickel foam, GO deposited in nickel foam, N-rGO@NF, and N-rGO@NF electrodes (1.0 cm×1.0), (b) 10 Digital photographs: (1) N-rGO@NF sheet was put into 1 M FeCl<sub>3</sub> at room temperature dissolve the Ni metal and (2) a whole N-rGO sheet without Ni foam support after nickel etching

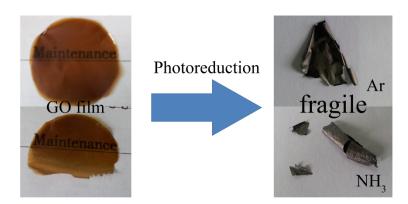


Fig. S2 Photograph of film before and after irradiated by a high-pressure Hg lamp (500 W) in Ar and NH<sub>3</sub> atmosphere.